

TZA-JING GUNG

Group Vice President
General Manager, Metal and Atomic Layer Depositon and Etch Products
Semiconductor Products Group
Applied Materials Fellow

Tza-Jing Gung is Group Vice President and General Manager of the Metal Deposition Products (MDP), Atomic Layer Deposition and Etch business units and an Applied Material Fellow. Under his leadership, MDP has more than doubled their revenue and hit record gross margin achievements.

Dr. Gung Tza-Jing has held various roles of increasing responsibility in MDP, Etch and Dielectric Deposition Products (DDP) business units. He previously was General Manager of the Chemical Vapor Deposition (CVD) division within DDP, responsible for CVD product technology, application development and market share growth. Before joining CVD, Dr. Gung led the Etch Strategic Products Group to achieve successful penetration for Mesa and Producer products at TSMC.

Dr. Gung first joined Applied Materials in 1999 to work on MDP, developing critical technologies for physical vapor deposition (PVD) that included high density DC plasma used to form conformal film, capillary-effect-assisted metal-filling technology, and self-collimated bottom-up deposition with zero overhang and asymmetry. He has also led groups in PVD and CVD.

Dr. Gung received his Ph.D. in electrical engineering and Computer Science from the Massachusetts Institute of Technology. He holds more than 30 patents for PVD, CVD and Etch products.